# Interconnect Issues for a Compact Si-W Calorimeter

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#### Si/W ECal R&D Collaboration

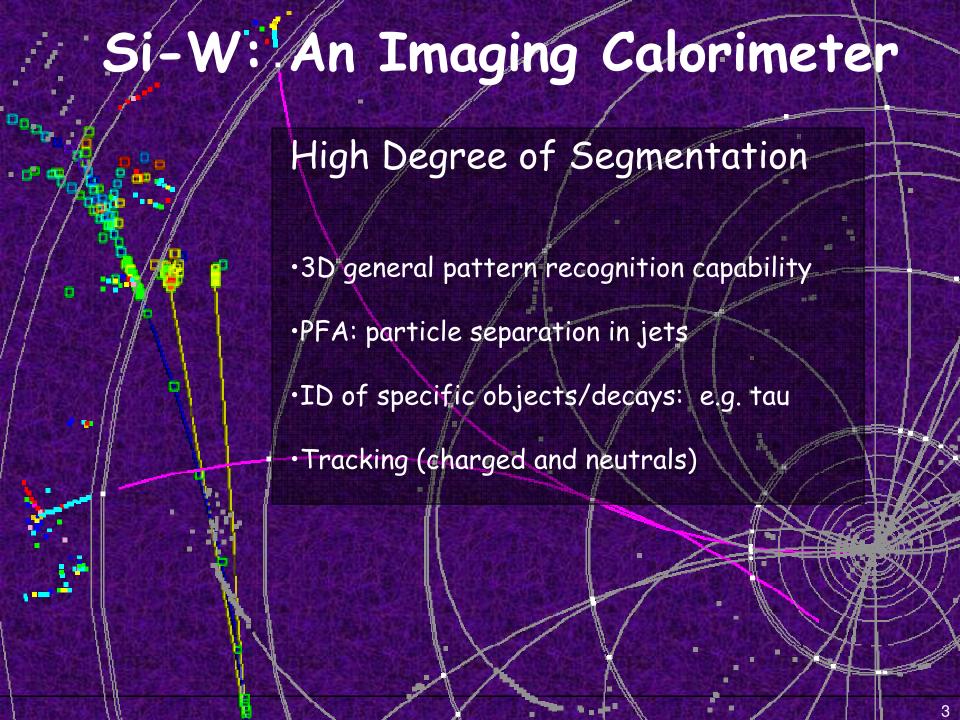
M. Breidenbach, D. Freytag, N. Graf, R. Herbst, G. Haller, J. Jaros, T. Nelson SLAC

B. Holbrook, M. Irving, R. Lander, M. Tripathi, M. Woods. University of California, Davis

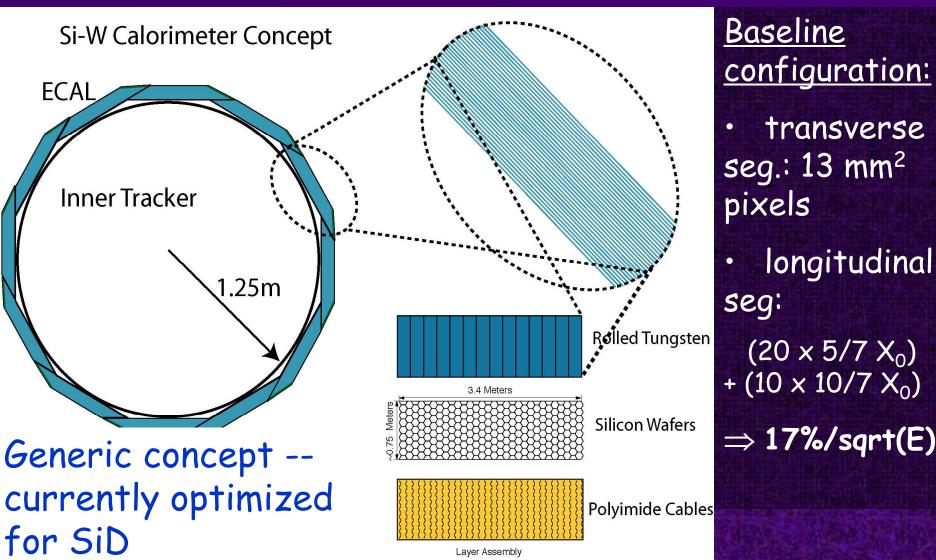
J. Brau, R. Frey, D. Strom. University of Oregon

V. Radeka Brookhaven National Lab

S. Adloff, F. Cadoux, J. Jacquemier, Y. Karyotakis LAPP Annecy



# Si-W Calorimeter Concept



configuration:

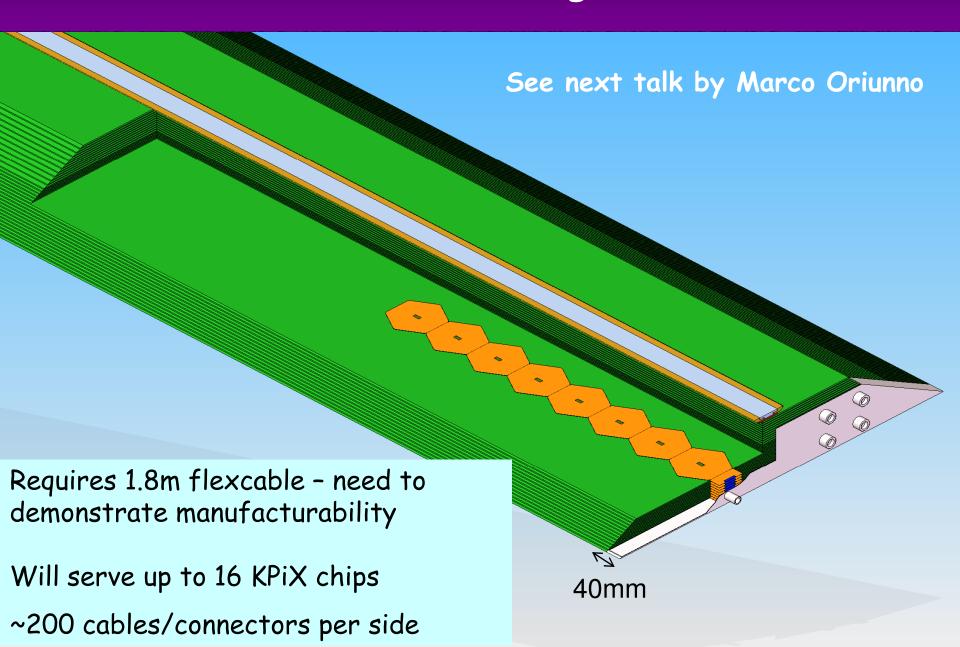
- transverse

$$(20 \times 5/7 X_0)$$
  
+  $(10 \times 10/7 X_0)$ 

 $\Rightarrow$  17%/sqrt(E)

 $\cdot$  1 mm readout gaps  $\Rightarrow$  13 mm effective Moliere radius

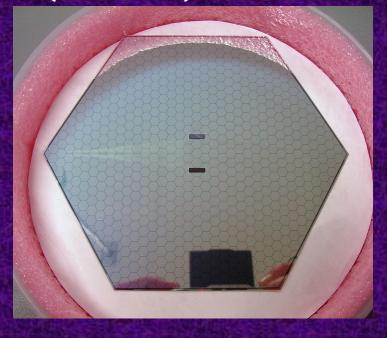
# Module Design

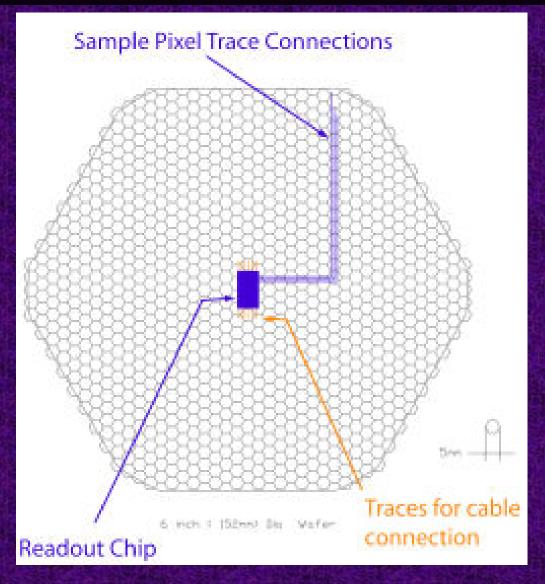


#### Si Detector

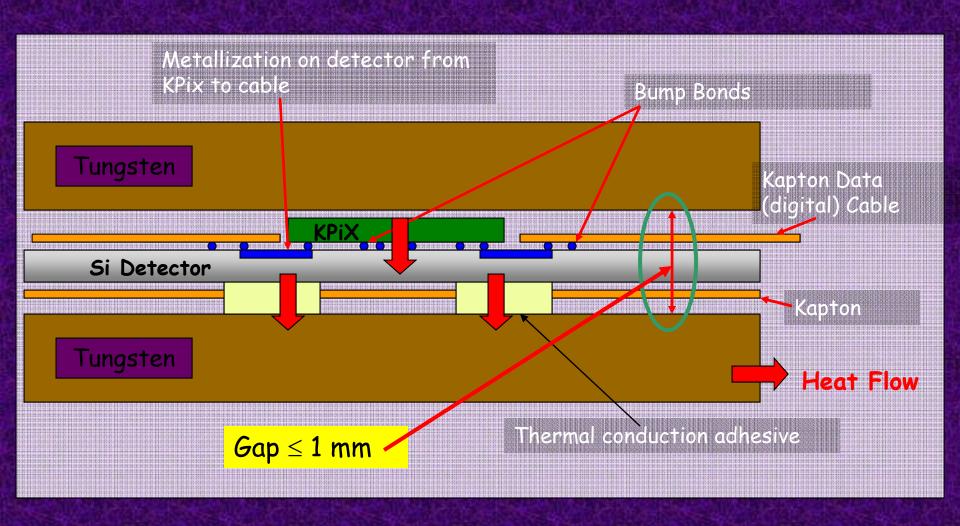
#### Wafer

- ·6 inch wafer
- · 1024 13 mm² pixels
- Hamamatsu Prototype(ver2) sensors in hand(40 wafers)



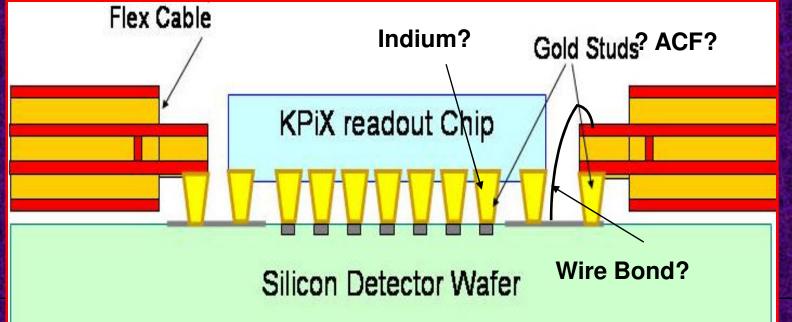


# Readout gap cross section (schematic)



# Interconnect issues: Technologies being considered

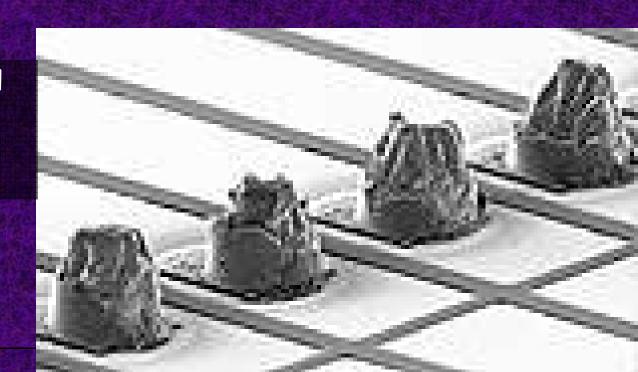
|                      | Prototyping                                       | Production          |
|----------------------|---|---------------------|
| KPiX to Sensor       | Gold Stud Bonding                                 | Indium Bump Bonding |
| Flex Cable to Sensor | Wire Bonding<br>Conducting Epoxy<br>ACF/Gold Stud | ACF Bonding         |



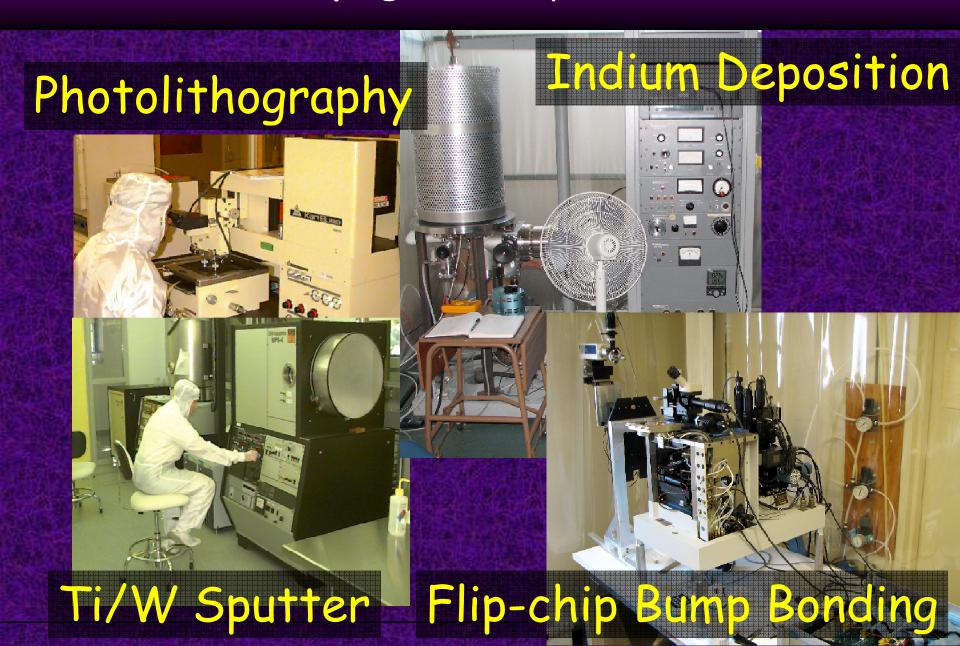
# Indium Bump Bonding

Indium Bump Bonding is a mature/commercial technology. UC Davis has developed the process for prototyping purposes. The campus operates a Class 100 clean room (10,000+ sq. ft.) and several pieces of specialized equipment.

Recent ARRA funding will significantly upgrade the lab and its capabilities.



# Indium Bumping: All steps done in-house



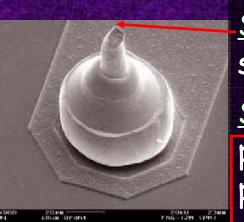
# Gold Stud Bump Bonding

- •An attractive option for prototyping because individual small chips are difficult to handle for Indium bumping.
- Several vendors (e.g. Palomar, K&S Accubump, West Bond).
- ·Upgraded Davis lab will have Gold Stud bumping capabilities.

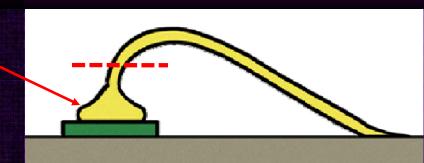


## Gold Stud Growth

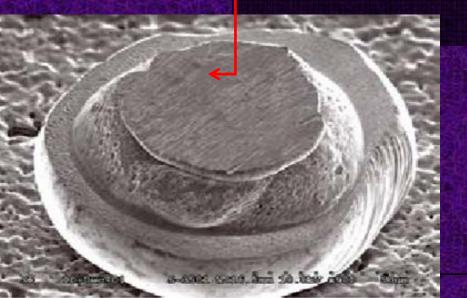
Step 1: A ~25  $\mu$ m gold wire is bonded to the pad.

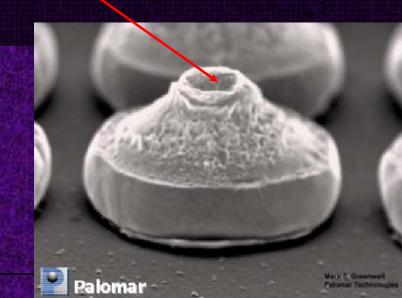


Step 2: The wire is snapped off.



Step 3: The stud is "coined" (flattened) to provide a better shape. Alternately, the wire is pushed back into the ball after snapping. The result is a matted surface.

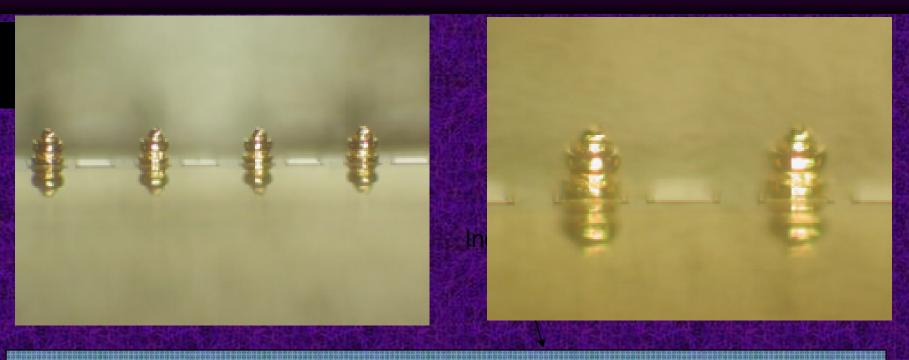




## KPiX with Gold Studs



# Double Studs



|         | <u>ball diameter - um</u> | <u>ball height - um</u> | <u>shear strength -</u><br>grams |  |
|---------|---------------------------|-------------------------|----------------------------------|--|
| count   | 10                        | 10                      | 10                               |  |
| average | 58.4                      | 66.0                    | 21.0                             |  |
| stdev   | 1.0                       | .76                     | 1.1                              |  |
| Cpk     | 1.8                       | 3.1                     | 1.8                              |  |

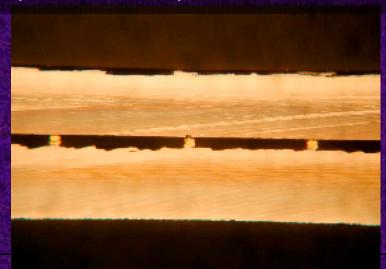
#### Adhesive Attachment

## Palomar Technologies:

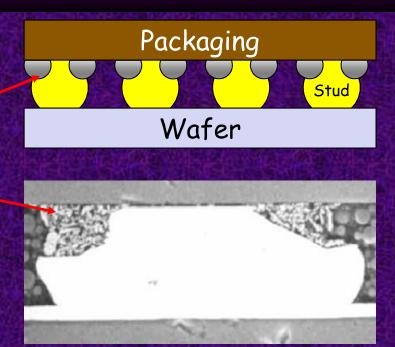
The tips of the studs are dipped into a conductive epoxy.

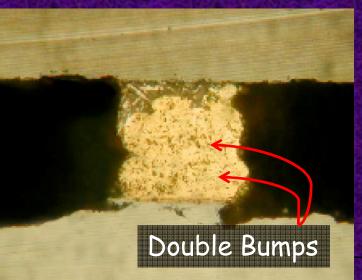
(Alternately, epoxy "dots" can be dispensed on the opposite wafer).

After a flip-chip alignment, the chips are compressed.

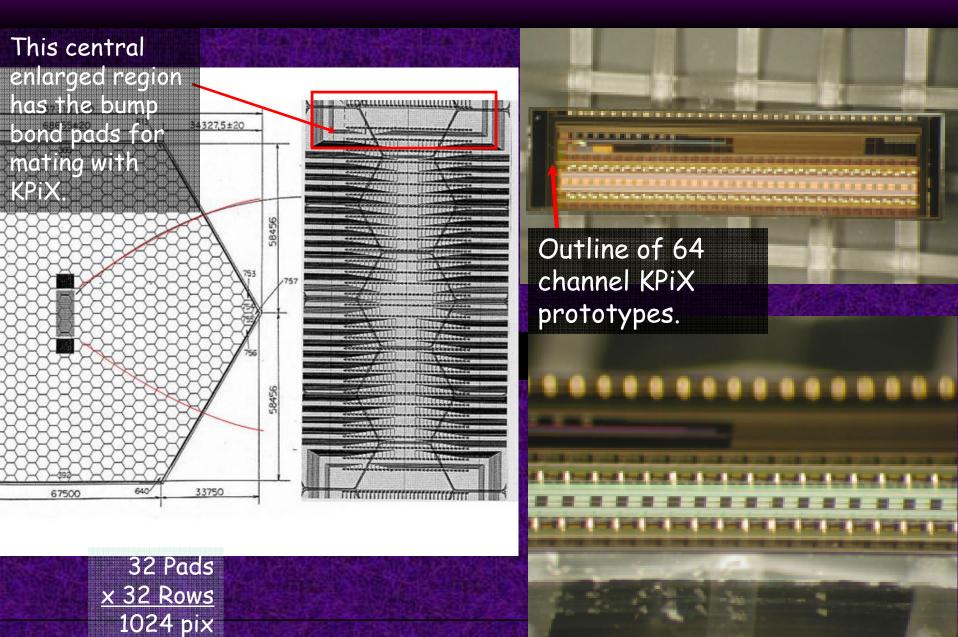


cross sections after slicing



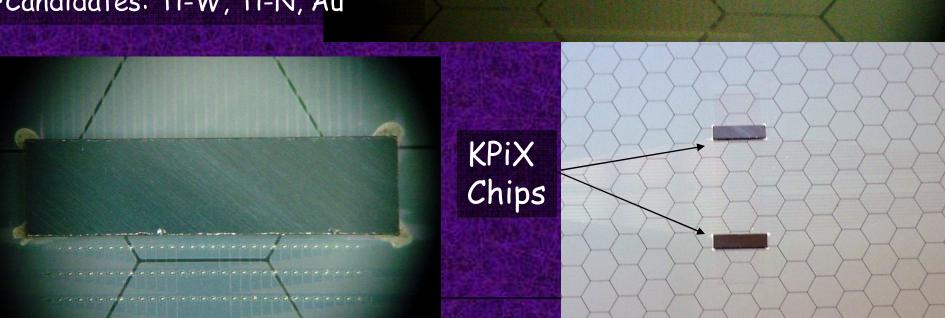


# Bump Bonding KPiX Prototypes



# Bump Bonding KPiX to Hamamatsu

- Initial gold-stud bump-bonding trials had mixed results due to surface oxidation.
- •Efforts underway to study optimum surface treatment of Hamamatsu wafers.
- ·Candidates: Ti-W, Ti-N, Au





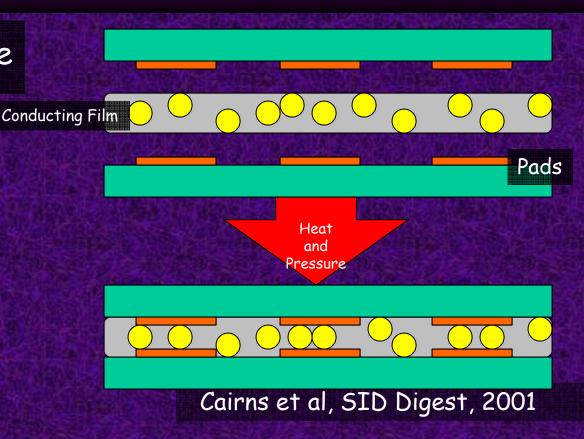
# Z-Axis Conducting Adhesive

3M: 7303 ACF Adhesive

~45  $\mu$ m particles ~75  $\mu$ m film thickness

≥250 µm pad pitch

Bonding Conditions: 140°C @ 260 PSI for 25 secs



Contact resistance  $\leq 0.2~\Omega$  (for flex-cable to PC board).  $\leq 0.2~\Omega$  maintained after 80°C for 1000 hours or 25°C for 4 yrs

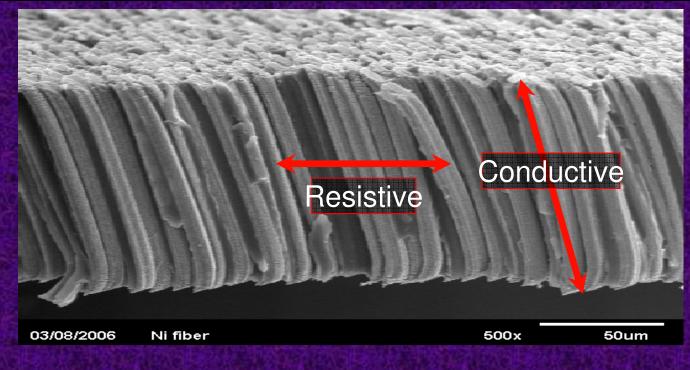
Flex cable to wafer attachment is not common => R&D.

## Thermoplastic Conducting Adhesive

#### **Btechcorp**:

Metal fibers in a matrix ~2 x 10<sup>7</sup> fibers/in<sup>2</sup>

Low Cure pressure: 50 psi

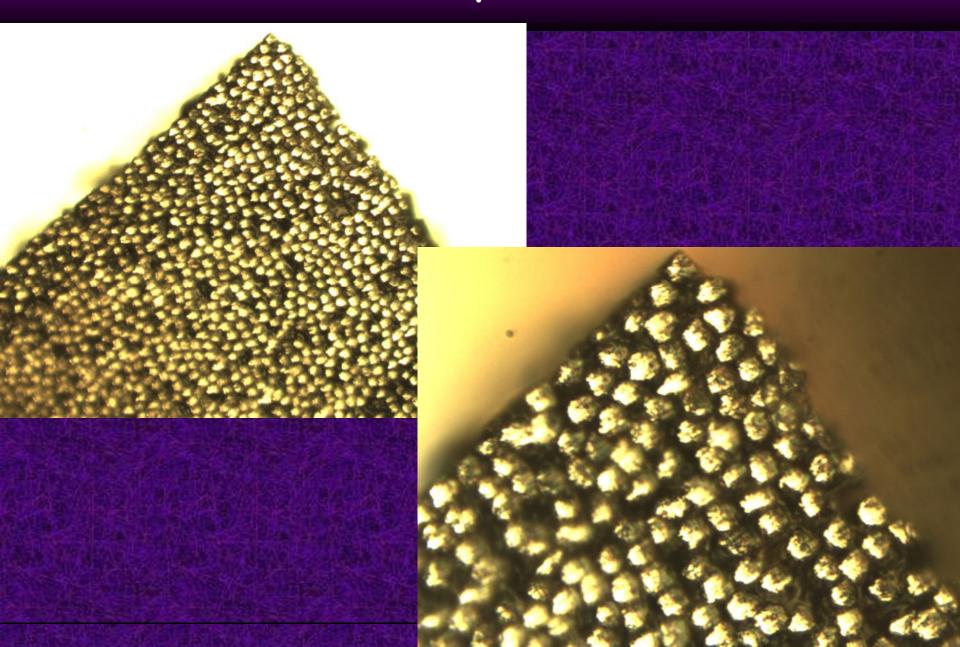


Nickel fiber structure.

Thermal Conductivity ≥ Cu. Smaller resistance

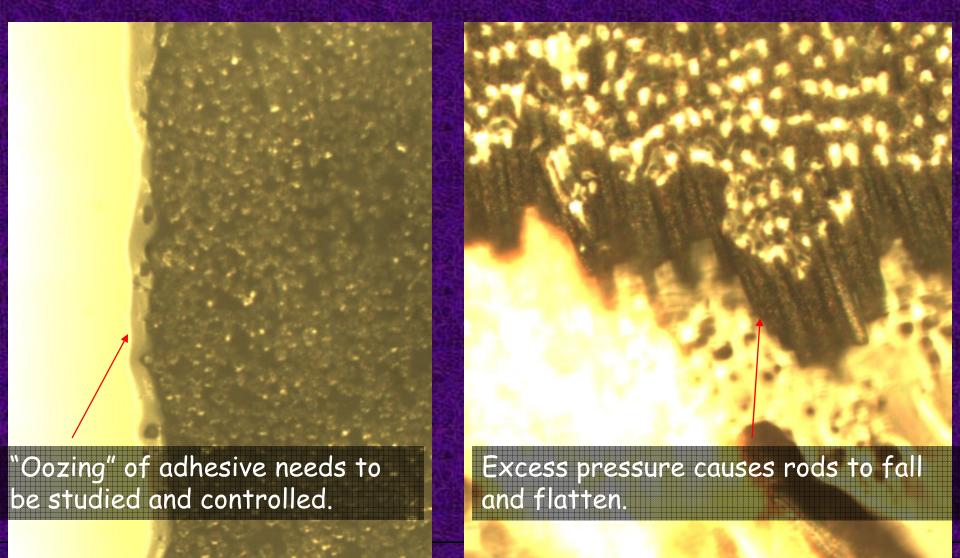
Cheaper.

# ACF Up Close

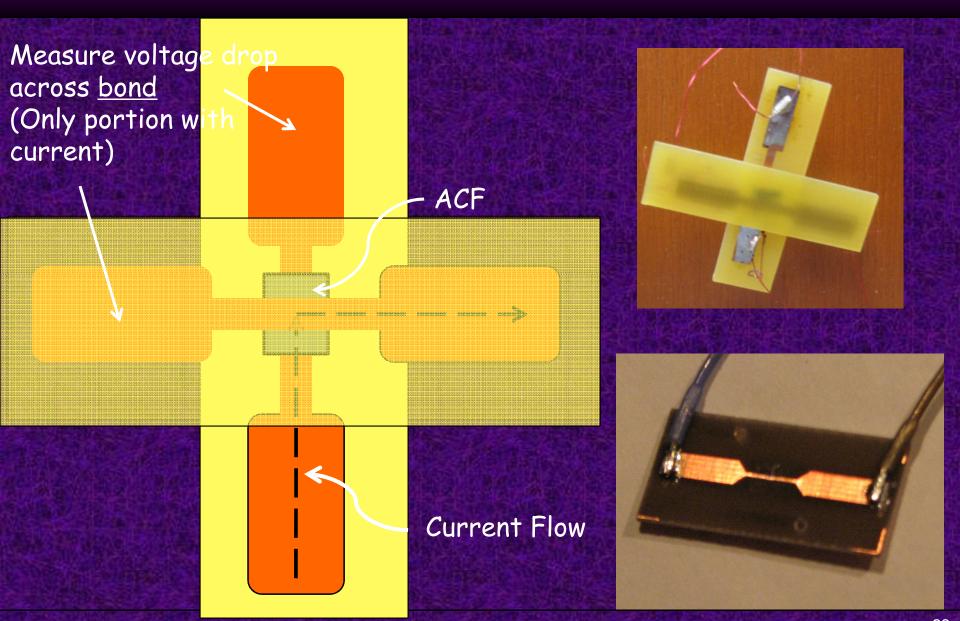


# Possible problems in ACF Bonding

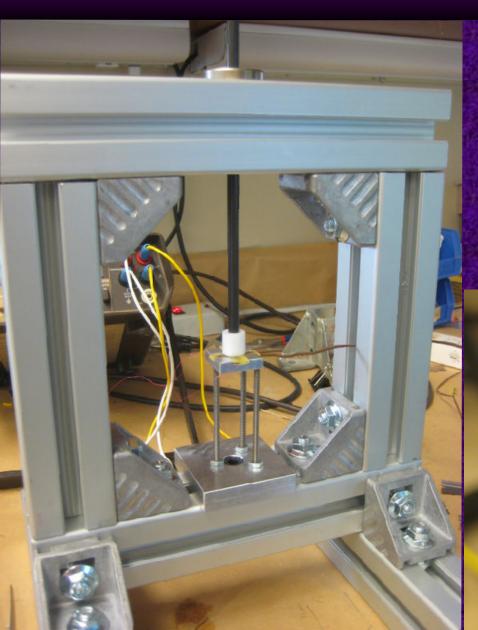
· ACF bonded to transparent glass allows for observation under a microscope



# Test Setup: "4 point" R measure

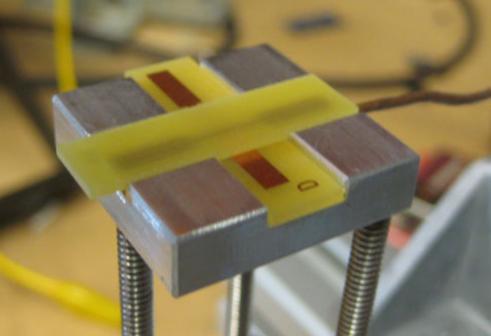


# Jig for Forming the Connection

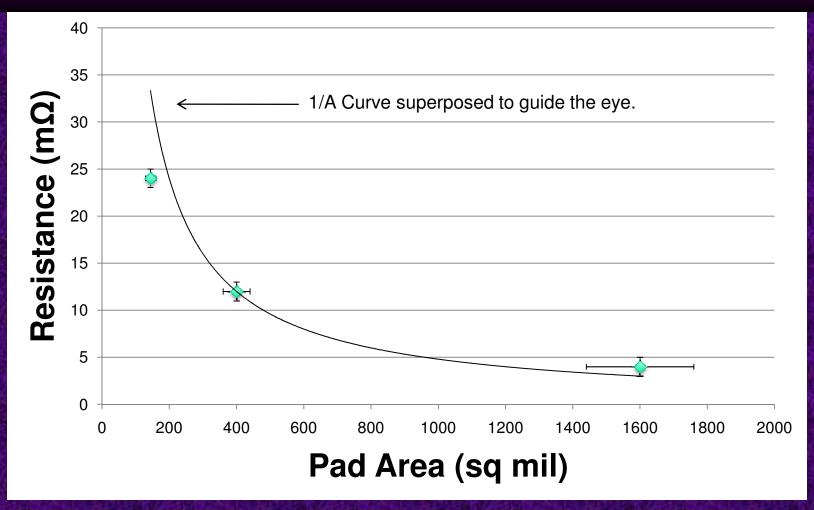


Temperature and pressure control and readback.

Duration and ramp-up/ramp-down are also factors.

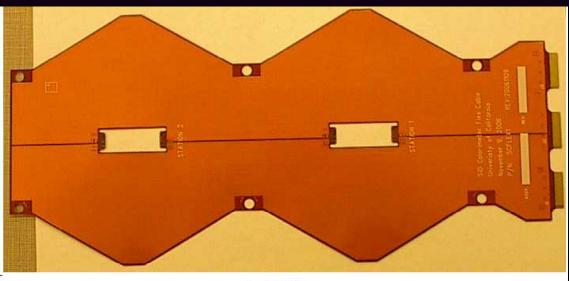


#### Initial Results



The results are promising. Goal for Flex Cable pads (100 sq mil) is ~100 m $\Omega$ , which is achievable.

#### Readout flex cable



LAYER 2 (MIDDLE)

CROSS SECTION OF AXIS - Y DIM XIO

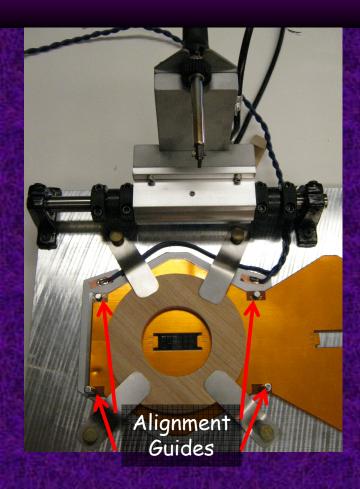
DATE: 08/09/06

FLEX CABLE PROTOTYPE

- Second prototype tested well with no problems:
  - 2 chip stations
  - Buried digital signal layer between power and ground planes
  - Two "lips" per KPiX from the buried layer.

- For 16 station cable:
  - A second vendor identified (produced long cables for EXO).

# Prototype Bonding Jig

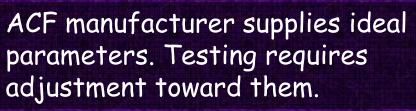


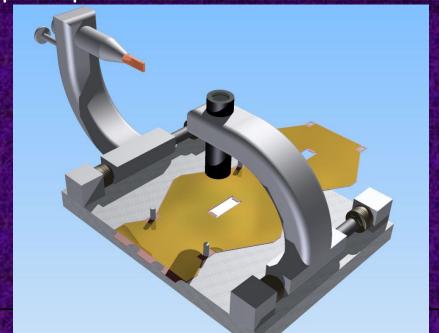
Swinging heating arm.

## Adjustable Factors:

- Preheat wafer
  Tip position
  and flex cable.
  Tip angle

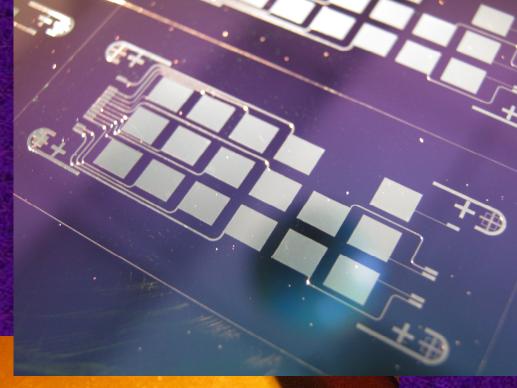
- Tip temp
- Pressure





#### Test Wafer

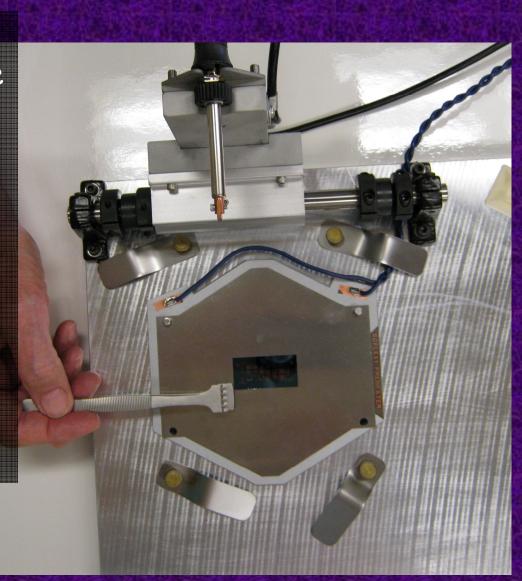
- Hamamatsu wafers too expensive to test on.
- Ti-W test wafer mimics the read portion of the Hamamatsu wafer.
- Large pads for read out where bump bond positions would be.





# Wafer alignment via EDM shim

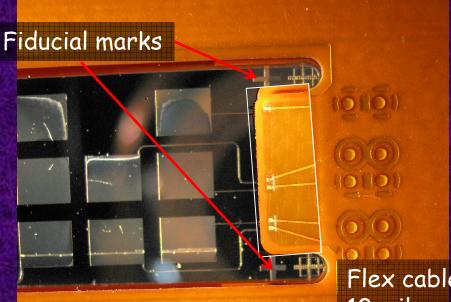
- A metal shim has been produced using precise electrical discharge machining
- Jig alignment posts hold metal shim in place.
- Shim holds wafer in cutaway.
- Guide posts align all pieces automatically.

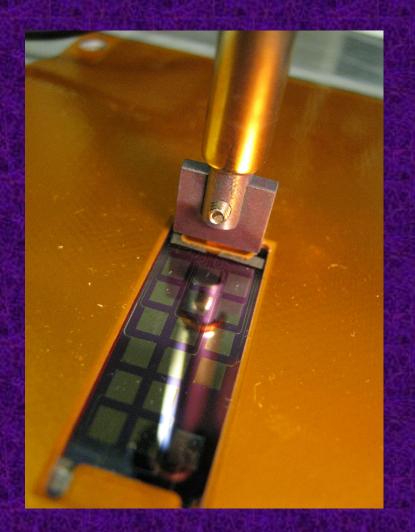


# Precision Alignment

 ACF does not need alignment.

 Flex cable and wafer do.



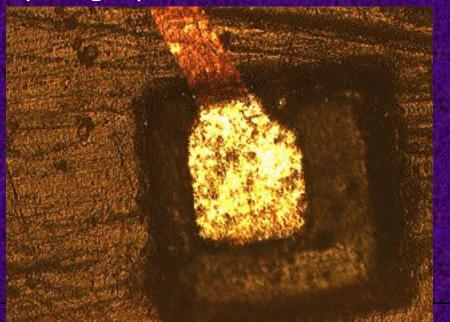


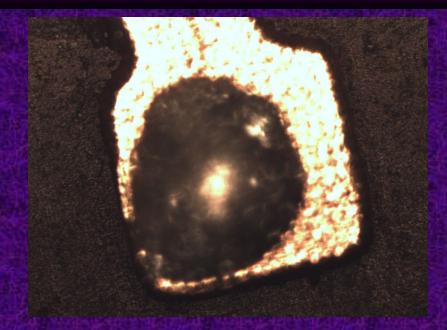
Flex cable pads revealed.

10 mil square pads

# Silver Epoxy

- A flaw in flex cable design was discovered. Groups of pads existed 20 µm deep in overlay well left over from gold deposition.
- Manual removal of overlay (young eyes).



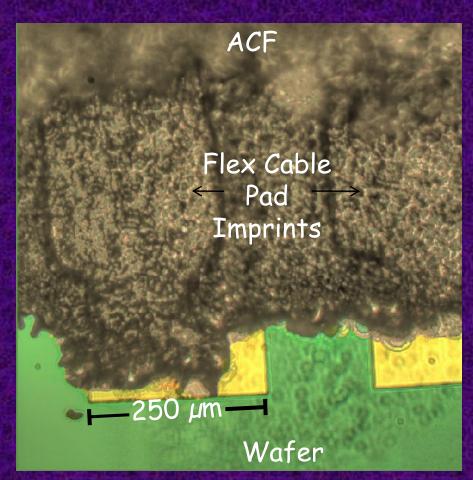


Successful flex cable to new gold test wafer. Continuity from wafer through flex cable for all channels.

### First results from ACF Attachment

 Flex cable and wafer do.

- Flex cable, jig, and wafer all align to ±20 microns.
- Full cable to be bonded in stages.



Indentation on ACF from Flex Cable pads after detachment of bonding surfaces.

## Summary

 The R&D for Si-W interconnect technology is progressing steadily.

#### Next Steps

- Further investigation of bonding parameters
- Silver Epoxy: study of surface metallization

#### Near-term Goal

Construct a "Tower": full-depth (30 layer), single-wafer wide module with 1024 channel KPiX chips bonded to sensor wafers and read out via flex cables. => Test Beam.

